

Low Temperature Synthesis and Sintering of UO_2 Nanoparticles

**International Conference on Sintering, 31 Aug 2011
Jeju Island, Korea**

**David B. Robinson
Sandia National Laboratories
Livermore, CA, USA**

UO₂ processing



UO₂(NO₃)₂

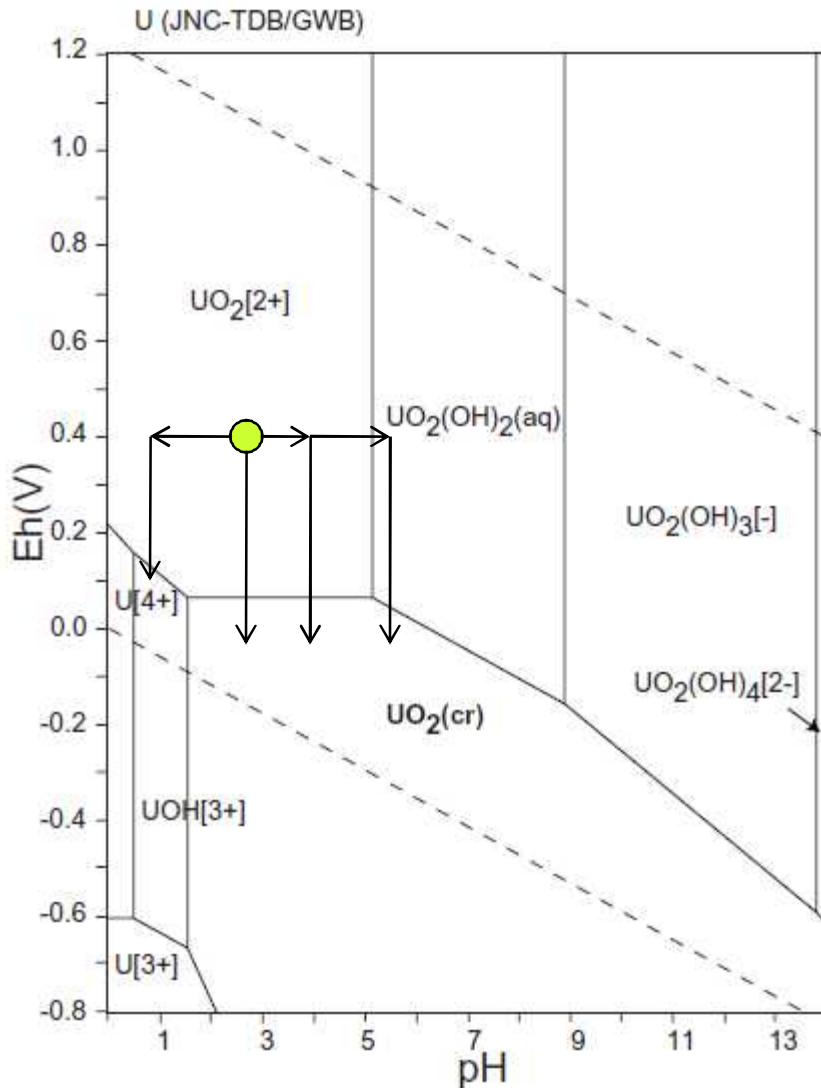


UO₂

Goals

- Understand how UO₂²⁺ becomes UO₂
- Develop more efficient processing with fewer high-temperature steps
- Minimize volatilization of actinides

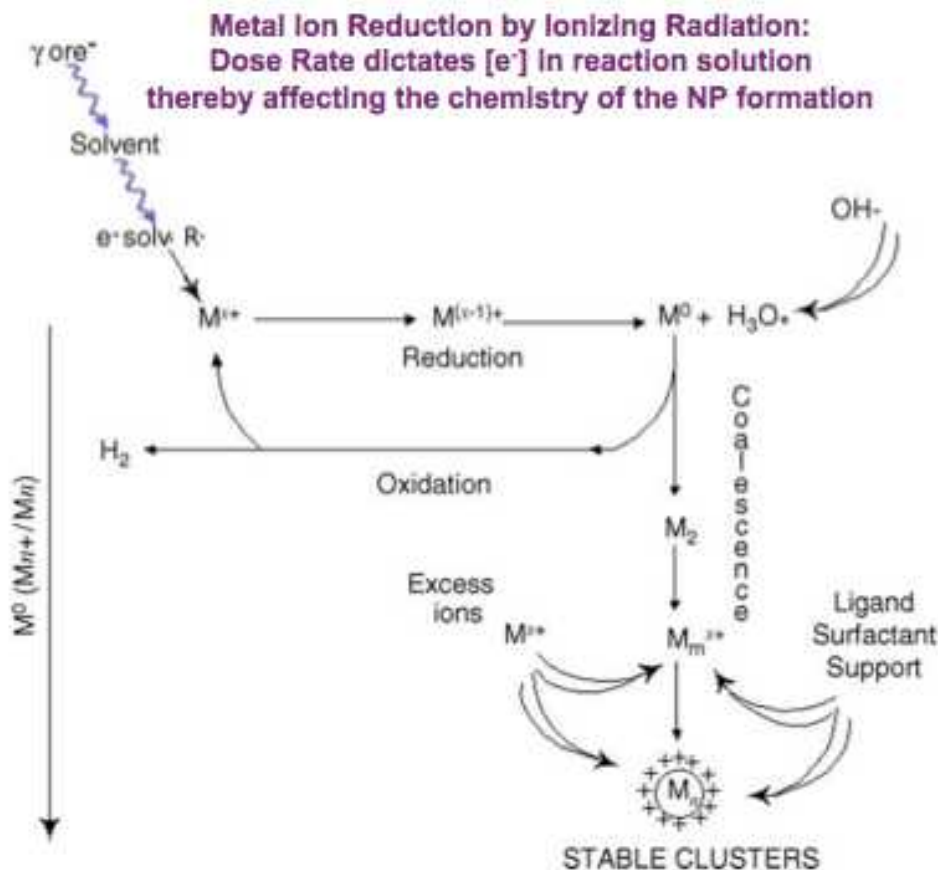
U Pourbaix diagram



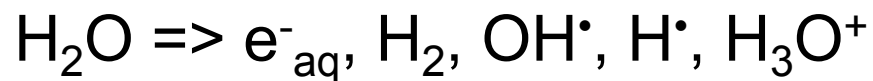
We use pH adjustment and gamma irradiation to find a convenient, high-yield path to UO_2

Then use heated-stage TEM to observe initial stages of sintering

Radiochemistry of Nanoparticles

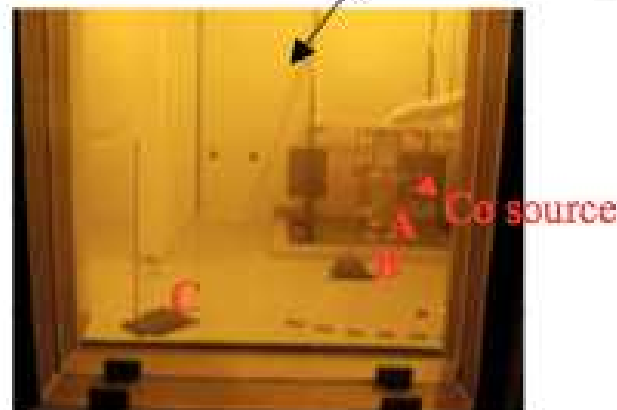
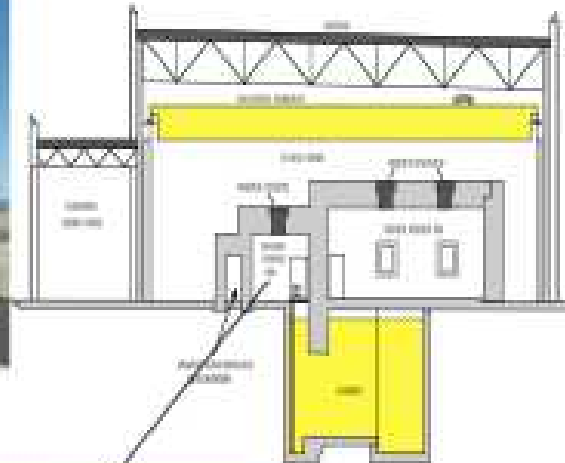


Gamma produces strong oxidizers and reductants (nonequilibrium)

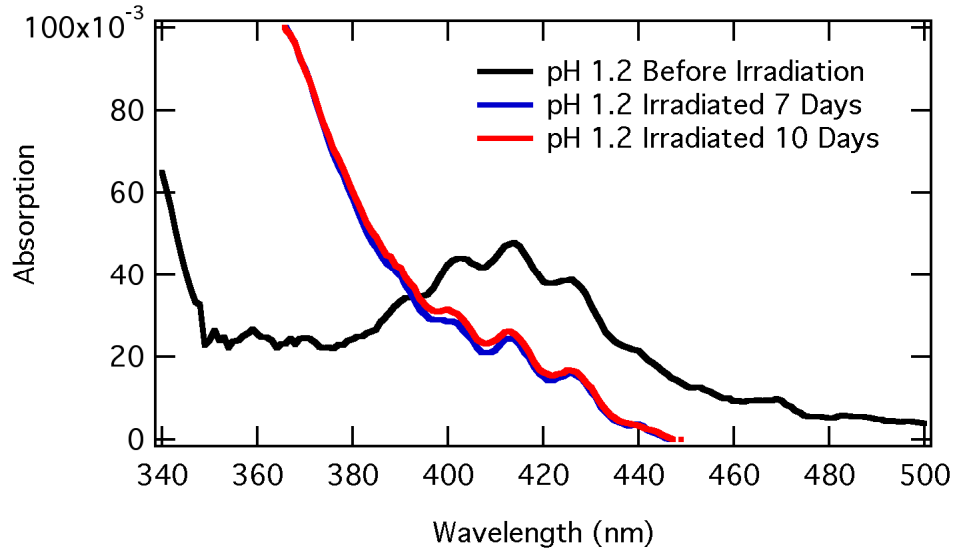


Sandia's Gamma Irradiation Facility

GIF: ^{60}Co source : 1.345×10^5 Ci

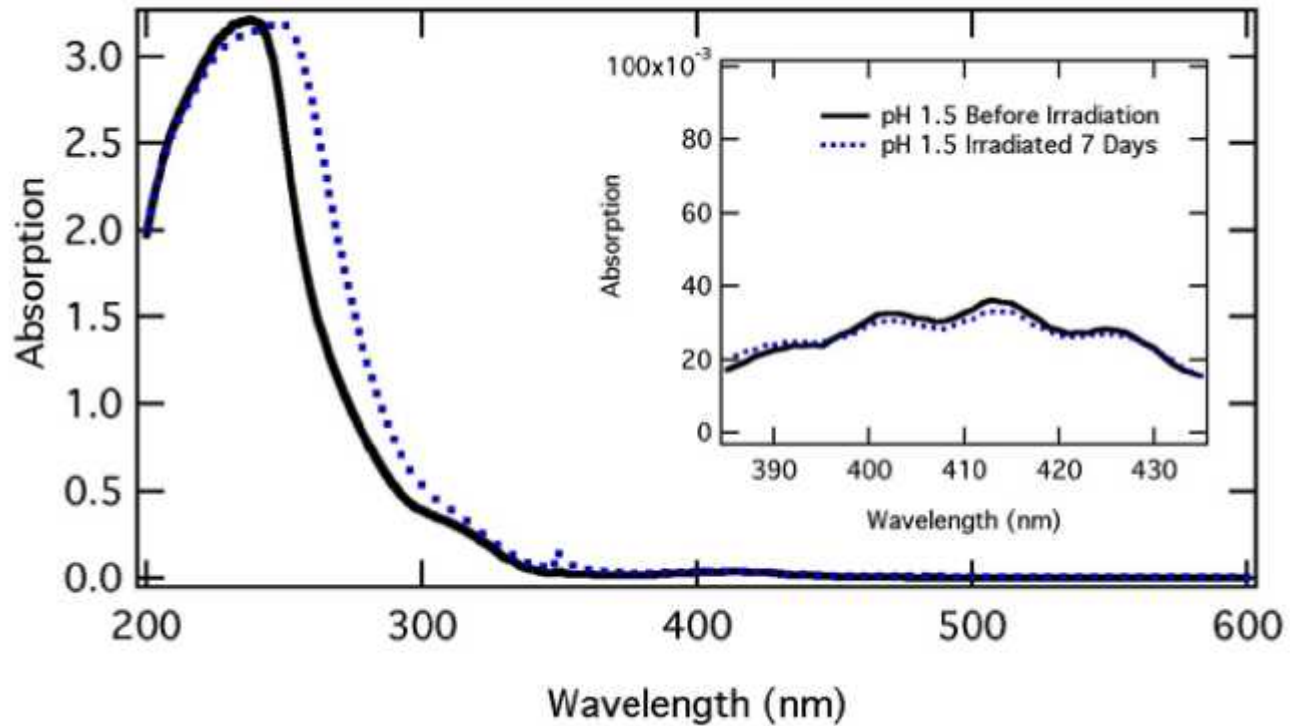


Strongly acidic conditions



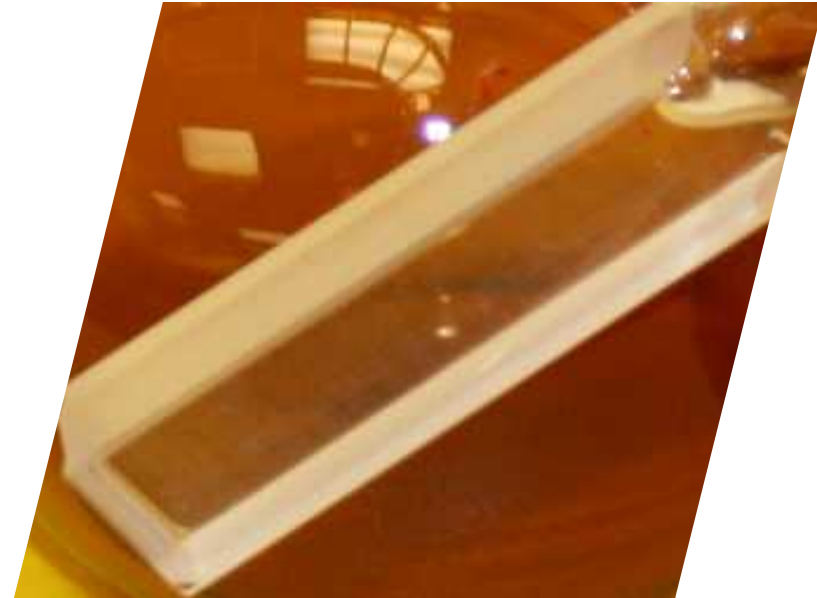
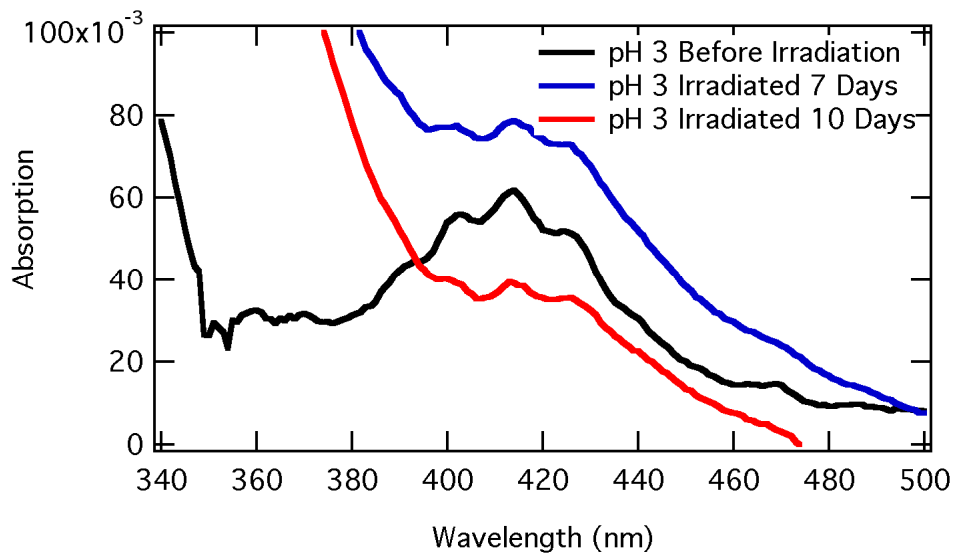
Incomplete reaction

Chloride vs. nitrate



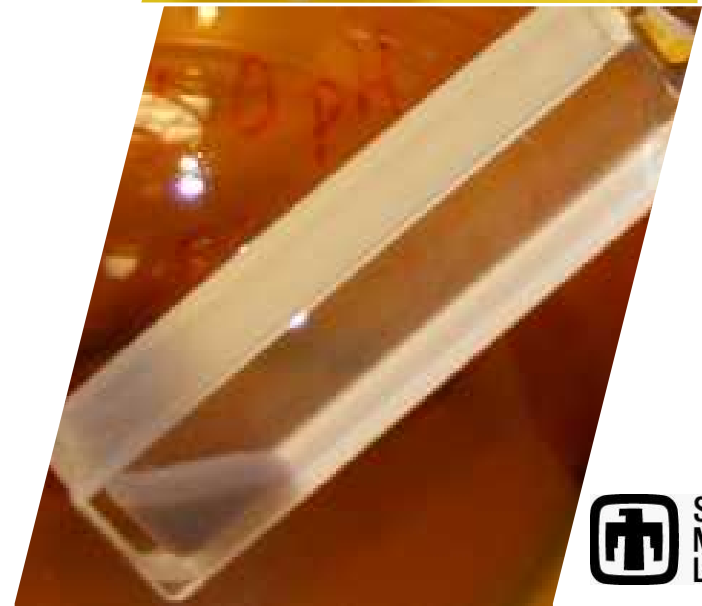
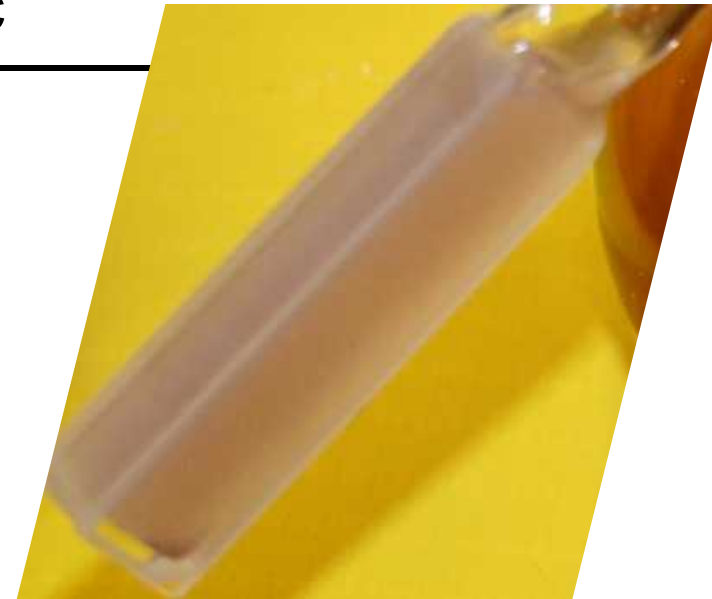
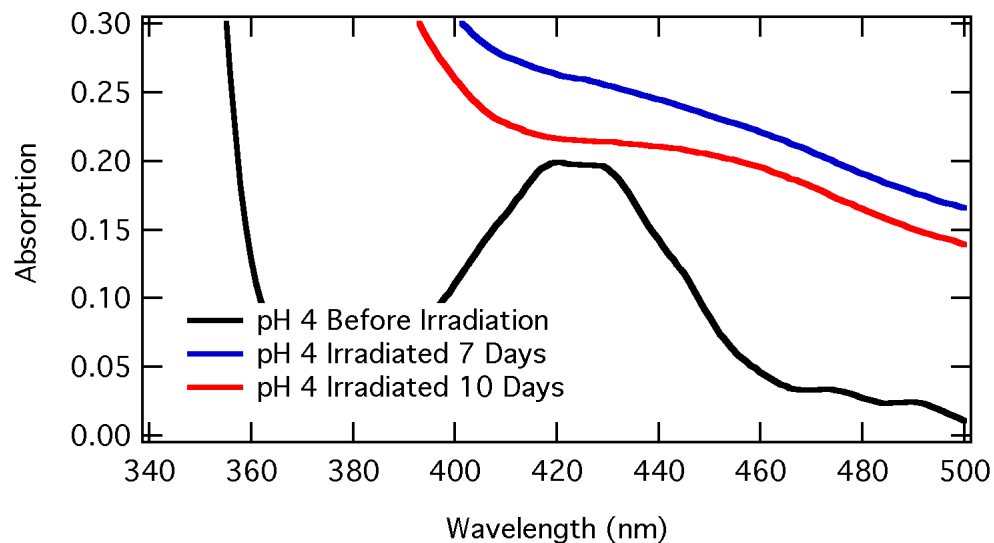
Chloride interacts differently with reactants

Acidic conditions



Cloudier product

Weakly acidic



Precipitate forms
Different reactant species are
present

Protochips heated TEM stage

Old approach: resistive heating of entire stage

- Requires cooling water, which frequently clogs
- Severe drift
- Noise/oscillation problems
- Slow ramp rates and settling

Protochips:

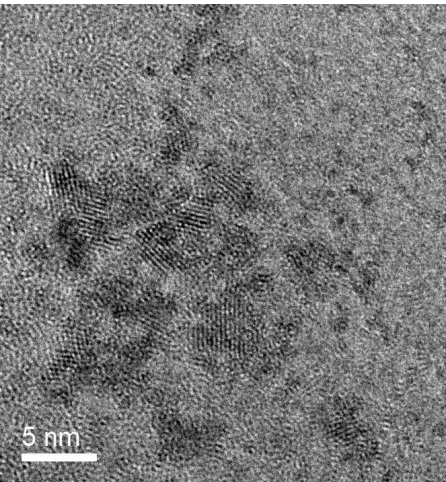
- Heat only a microfabricated grid
- Ramps 1000 C / ms, RT – 1200 C
- Also permits electrical measurement



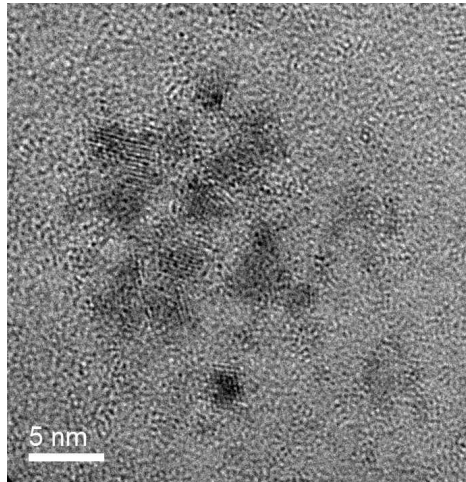


pH 3 heating

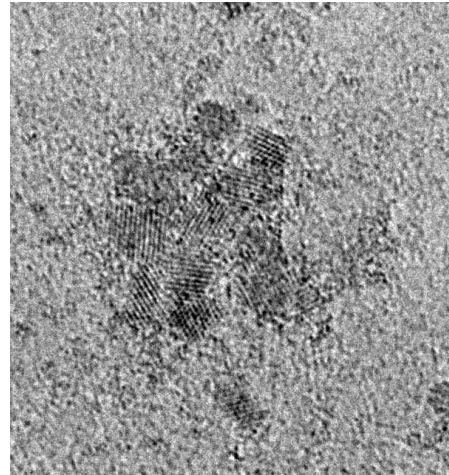
RT



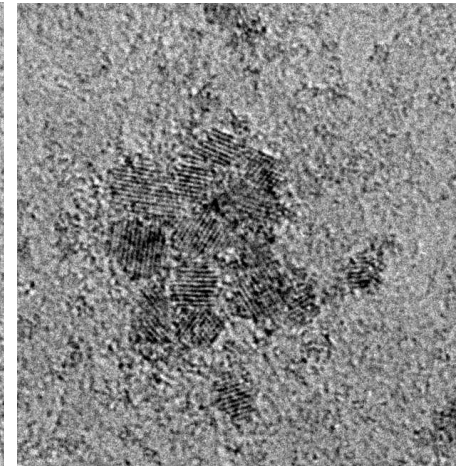
200 °C



400 °C



500 °C

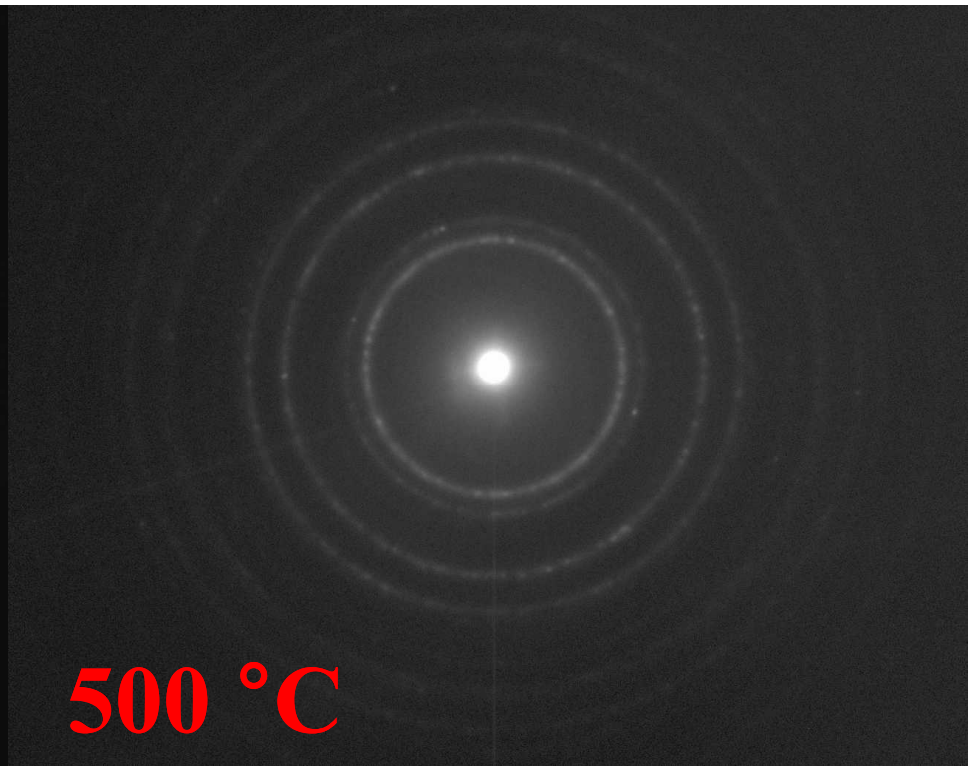


Consolidation is observed on TEM grid



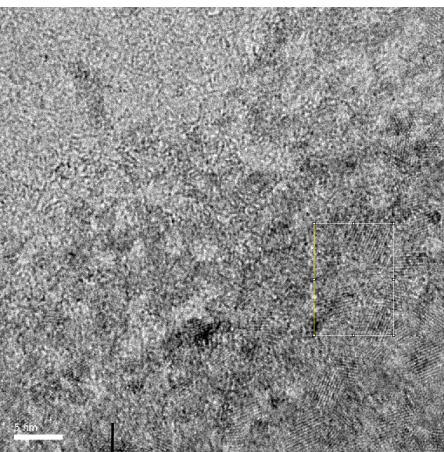
Electron diffraction patterns (pH 3)

Sharper lines indicate grain growth

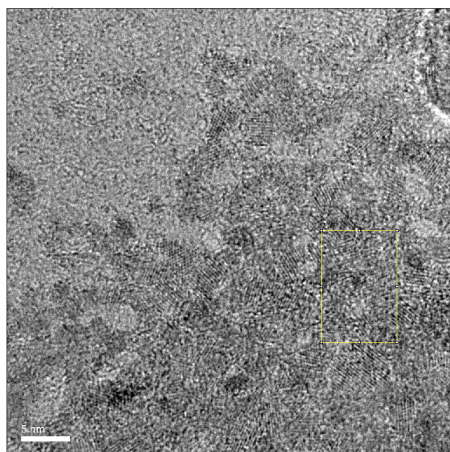


pH 1.5 heating (with chloride)

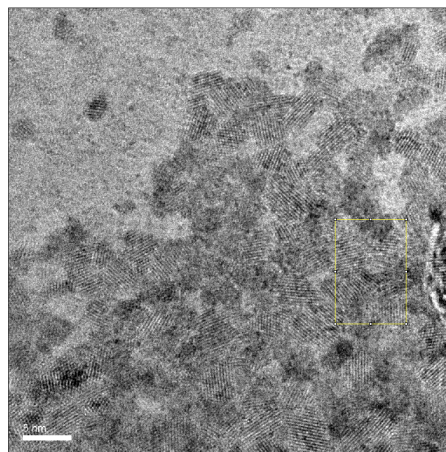
RT



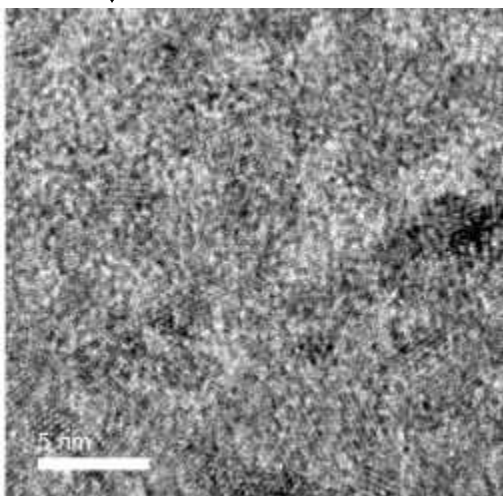
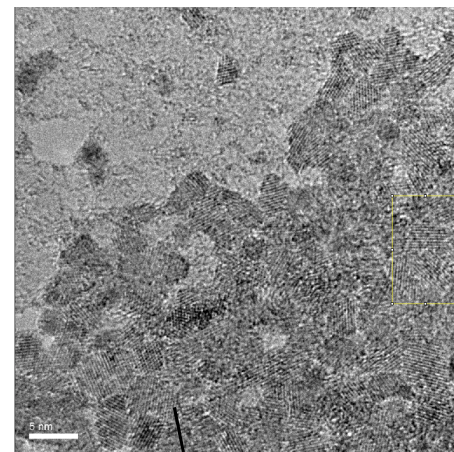
300 °C



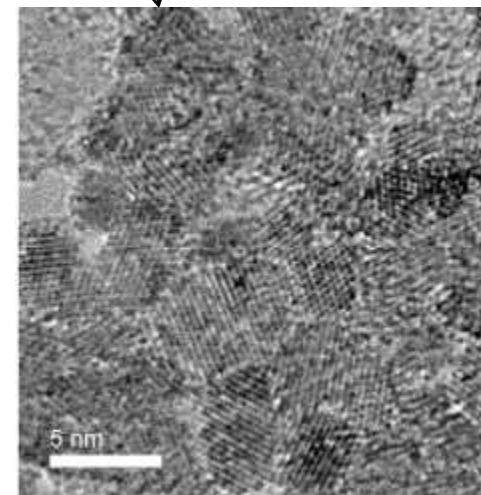
500 °C



600 °C



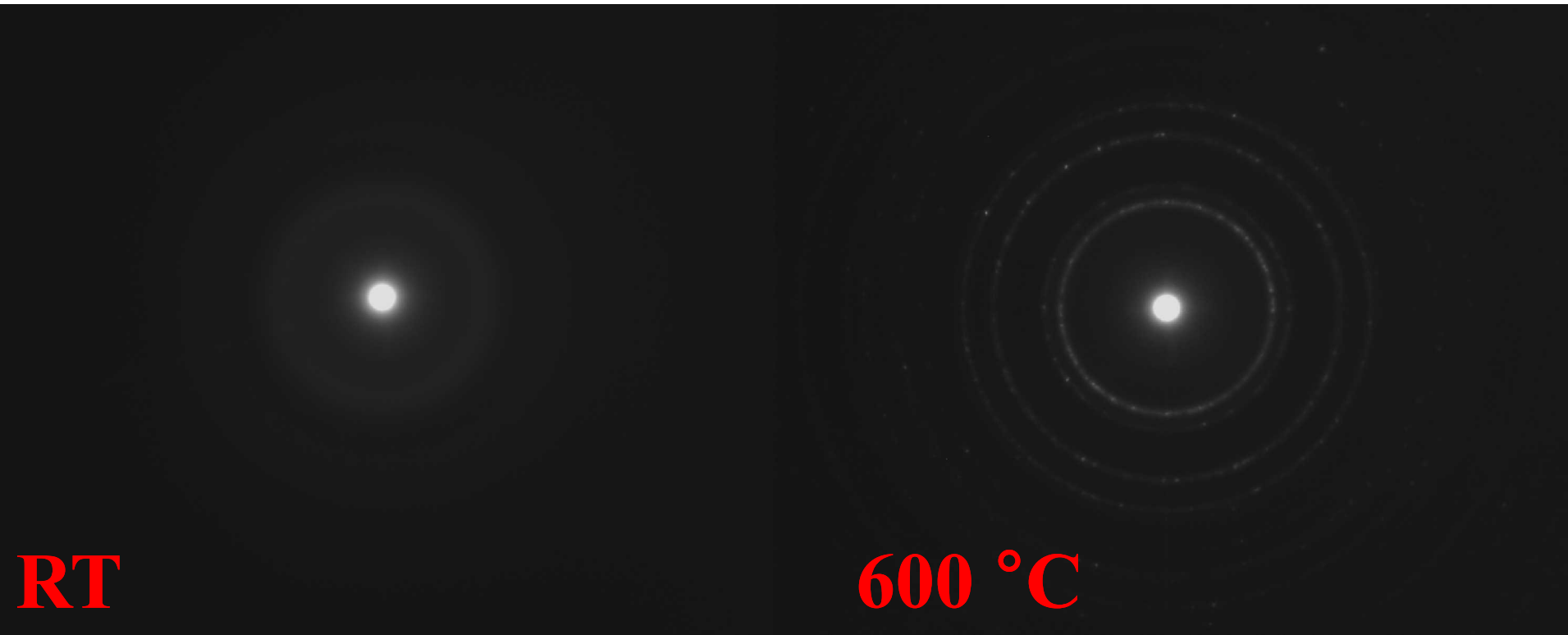
Likely a mixture of UO_2 and dried reactant
- still consolidates





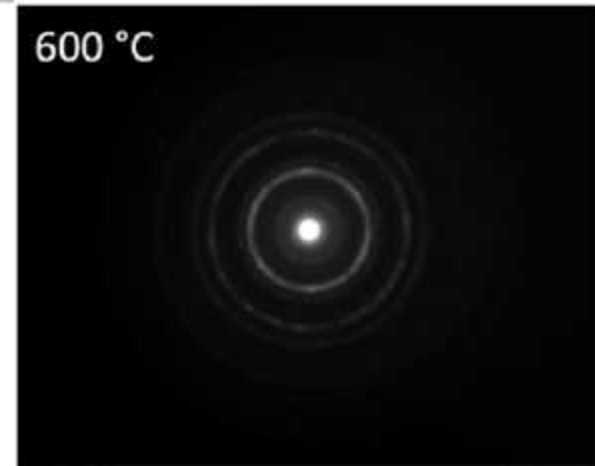
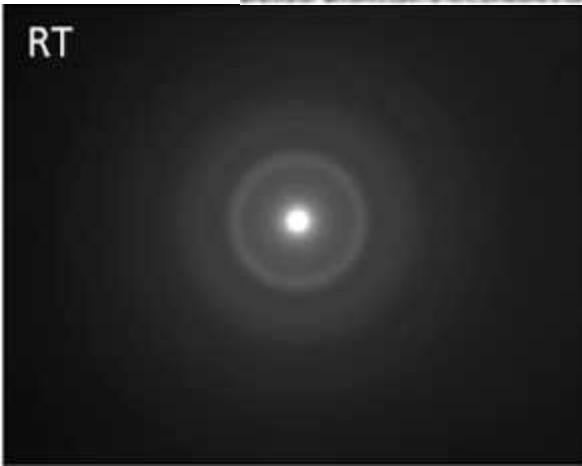
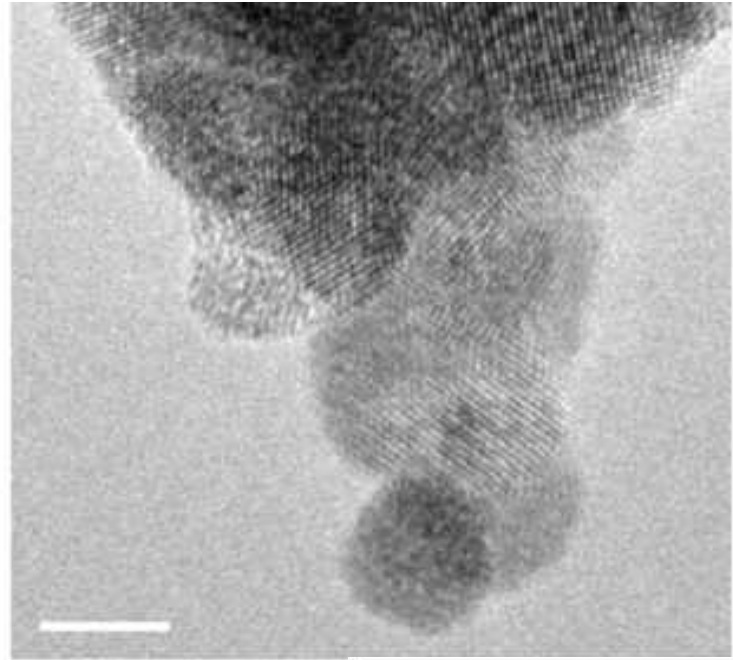
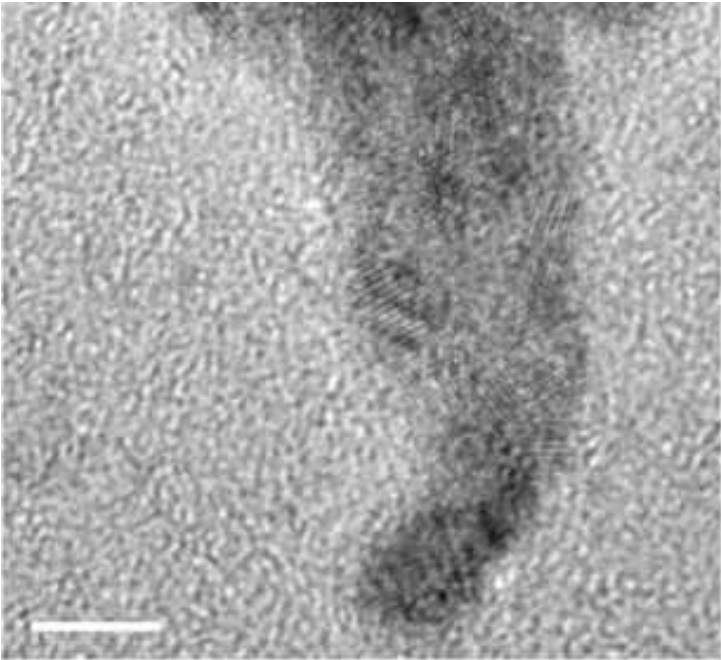
Electron diffraction (pH 1.5, chloride)

Grain growth is also observed, but less crystalline starting (and ending) point



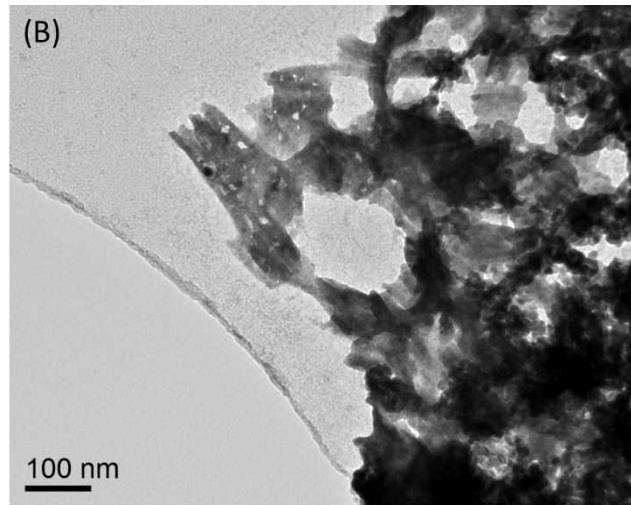
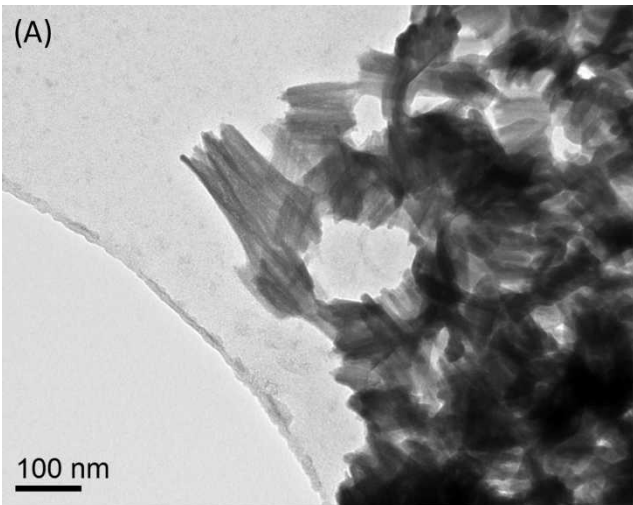


pH 4

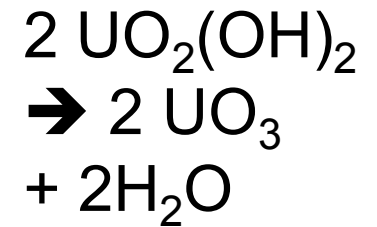


Clear grain growth

pH 4: Condensation



Holes form



Partial reactant precipitation at higher pH



pH 4 sintering movie

11-05-2010

U oxide

200 to 800 C

SF 4-9-8



pH 4 condensation movie

11-05-2010

U oxide

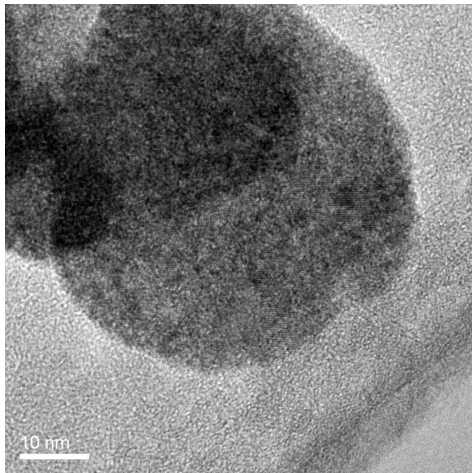
200 to 785 C

SF 4-9-8

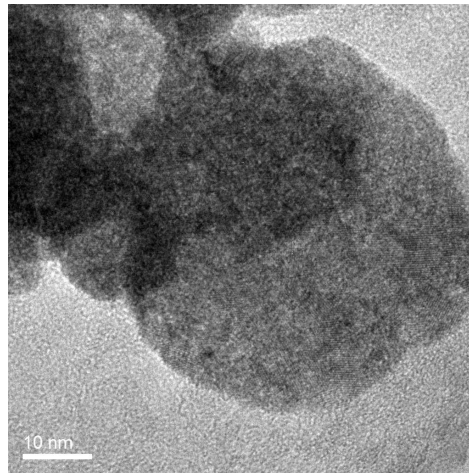


pH 5

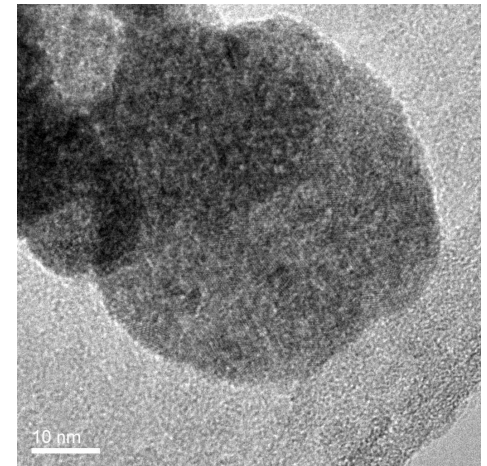
RT



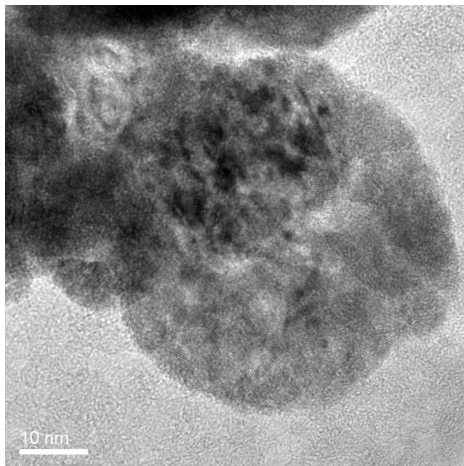
300 °C



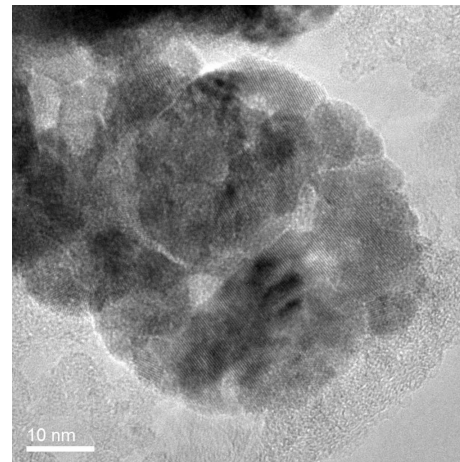
400 °C



600 °C



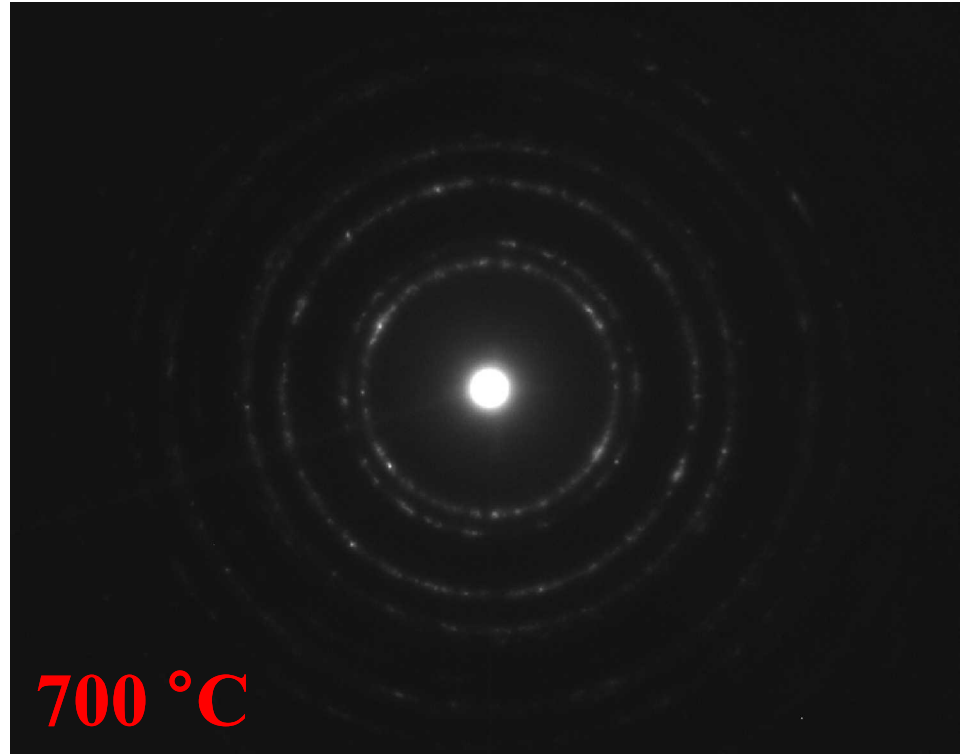
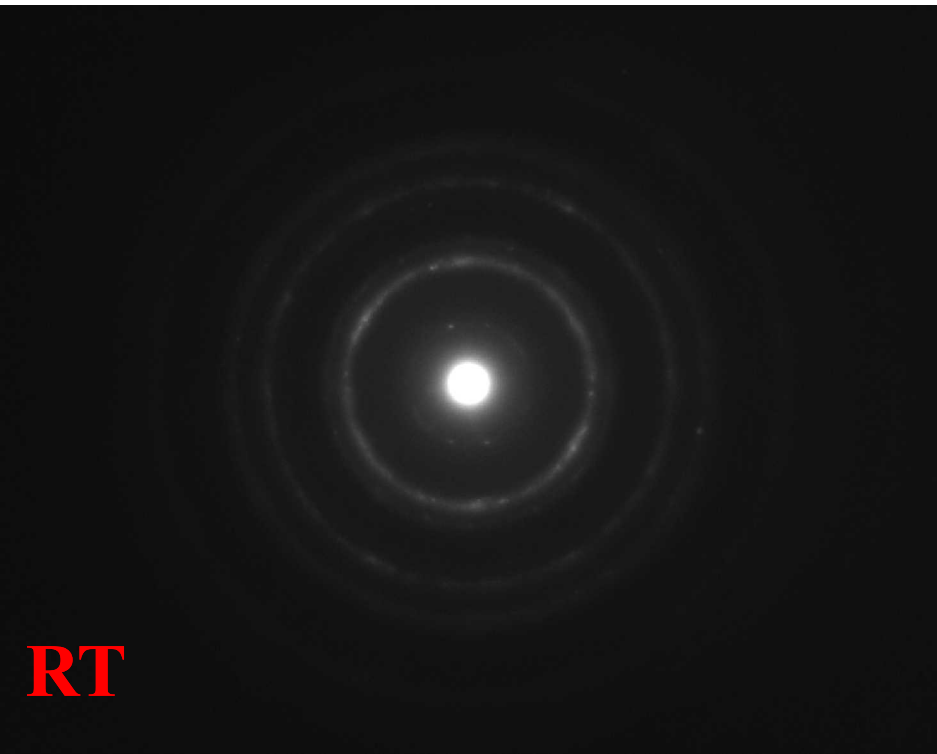
700 °C





Electron diffraction, pH 5

Similar sintering (and not just condensation)
occurs at pH 5





Summary and conclusions

Sandia (Albuquerque, NM, USA)

- UO_2 precipitation requires a balance between pH and reduction
 - Preferably avoid UO_2^{2+} precipitation, soluble U^{4+} , reoxidation
- UO_2 consolidates, UO_2^{2+} condenses upon heating
- Initial sintering processes occur well below bulk sintering temperatures (~ 1700 C)
- Product yield at low temperature can be optimized
- Initial low-temperature treatment may prove useful



Acknowledgements

Sandia (Albuquerque, NM, USA)

drobins@sandia.gov

Chemistry:

Tina M. Nenoff

Summer Ferreira

Veena Tikare

Gamma facility:

Donald J. Hanson

Electron microscopy:

Paula Provencio

Jianyu Huang

Ben Jacobs (Protochips, Inc., Raleigh, NC, USA)

